

Notice of References Cited	Application/Control No. 10/521,856		Applicant(s)/Patent Under Reexamination BLEES, MARTIN HILLEBRAND	
	Examiner Joshua D. Zimmerman		Art Unit 2854	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,403,397	06-2002	Katz, Howard Edan	438/99
	B	US-			
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	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Positive Microcontact Printing" E. Delamarche; M. Geissler; H. Wolf; B. Michel. J. Am. Chem. Soc. 2002, 124, 3834-3835
	V	"Defect-Tolerant and Directional Wet-Etch Systems for Using Monolayers as Resists" Geissler, M.; Schimd, H.; Bietsch, A.; Michel, B.; Delamarche, E., LANGMUIR 2002, 18, 2374-2377
	W	"Soft Lithography" Y. Xia; G. M. Whitesides ANGEW. CHEM. INT. ED. 1998, 37, 550-575
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.